

10/553677

JC09 Rec'd PCT/PTO 17 OCT 2005

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Shuichi OKAWA et al.

Application No.: New U.S. National Stage of
PCT/JP04/008232

Filed: October 17, 2005

Docket No.: 125685

For: MASK MATERIAL FOR REACTIVE ION ETCHING, MASK, AND DRY ETCHING
METHOD

PRELIMINARY AMENDMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

Please consider the following:

Amendments to the Specification;

Amendments to the Claims as reflected in the listing of claims;

Remarks.